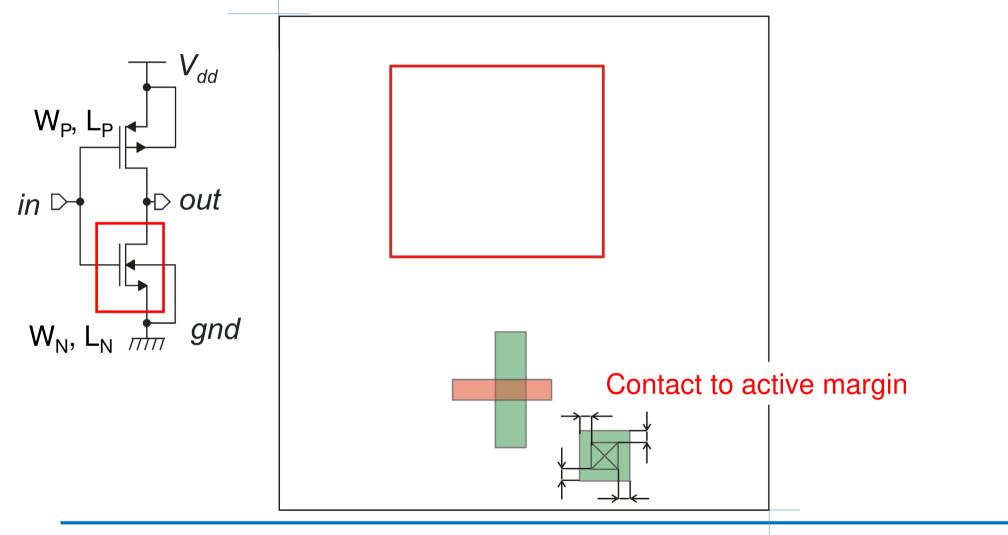
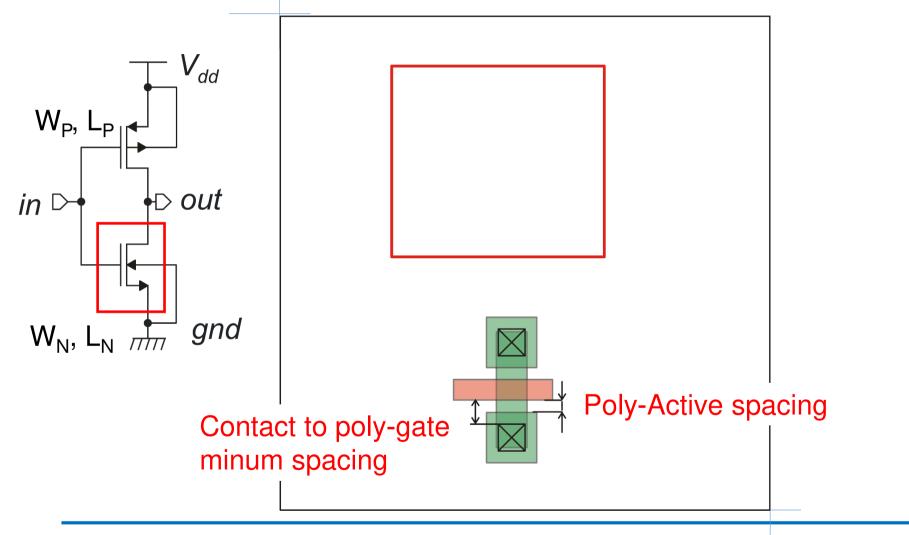


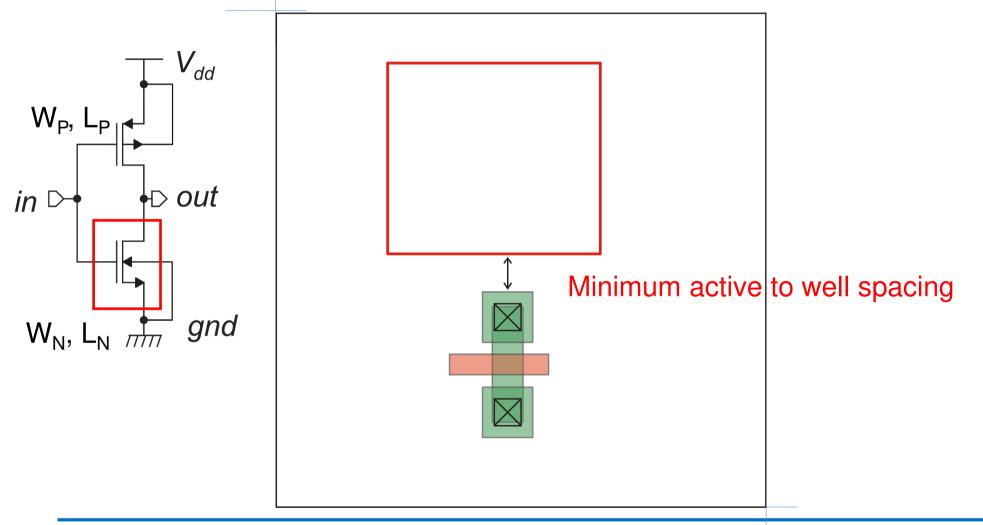
### Then, we provide enough active surround to the contact



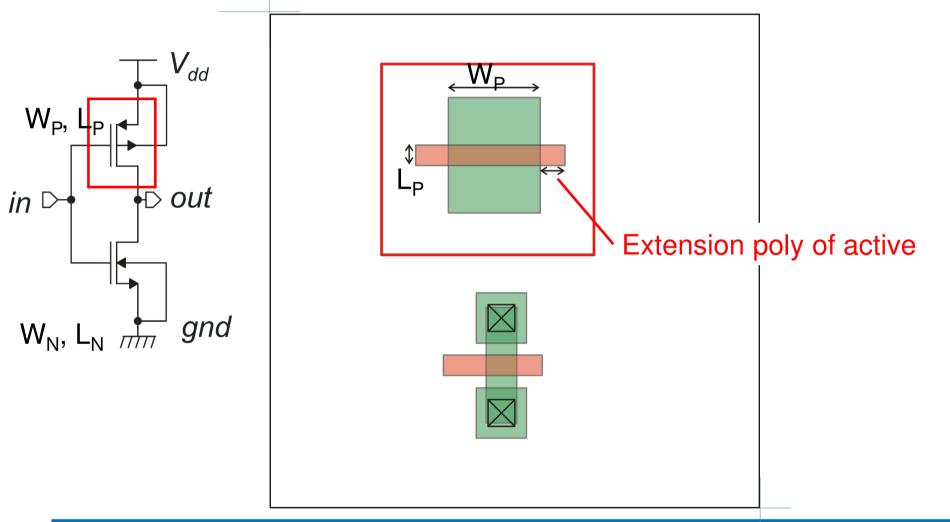
### Then, we provide enough active surround to the contact

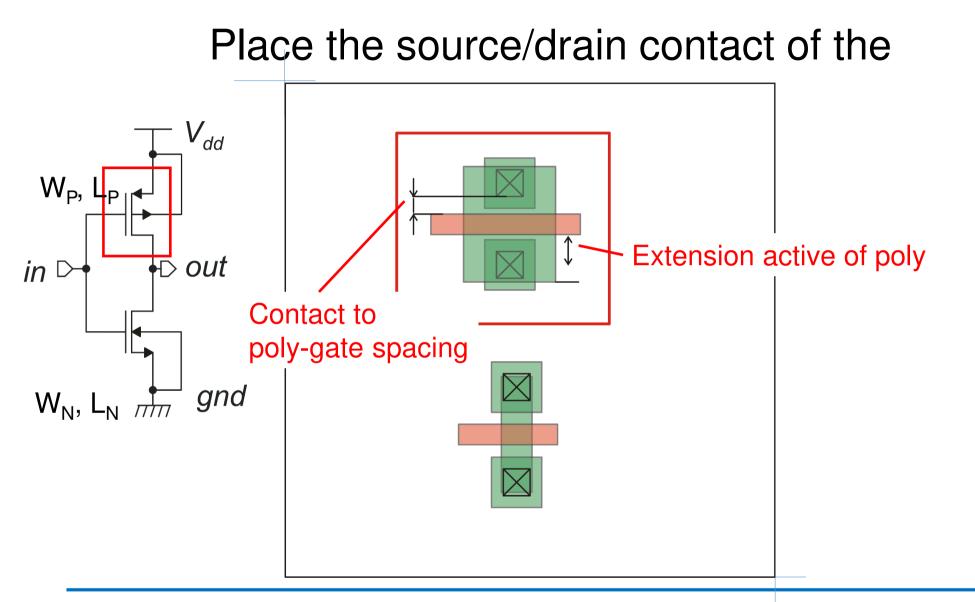


## Place the n-MOS as close as possible to the n-well

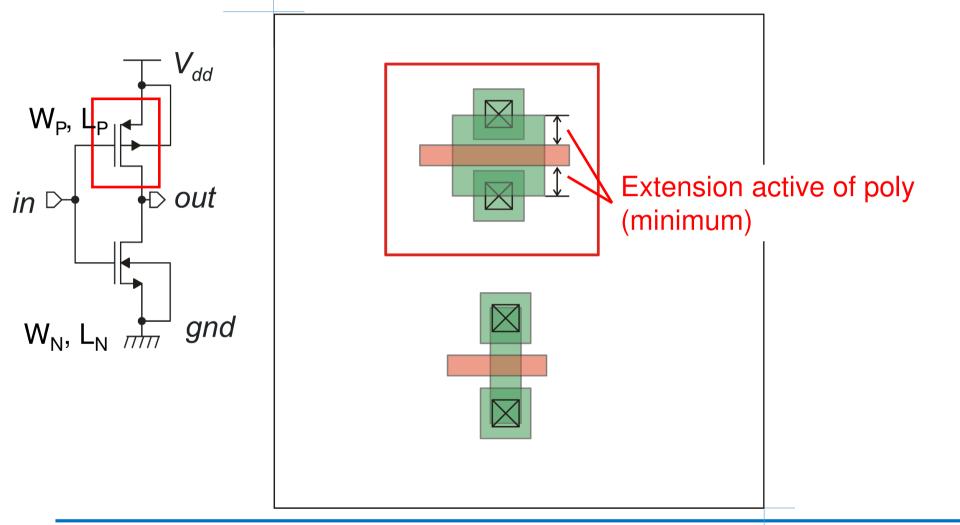


# Now draw the p-MOS inside the n-well

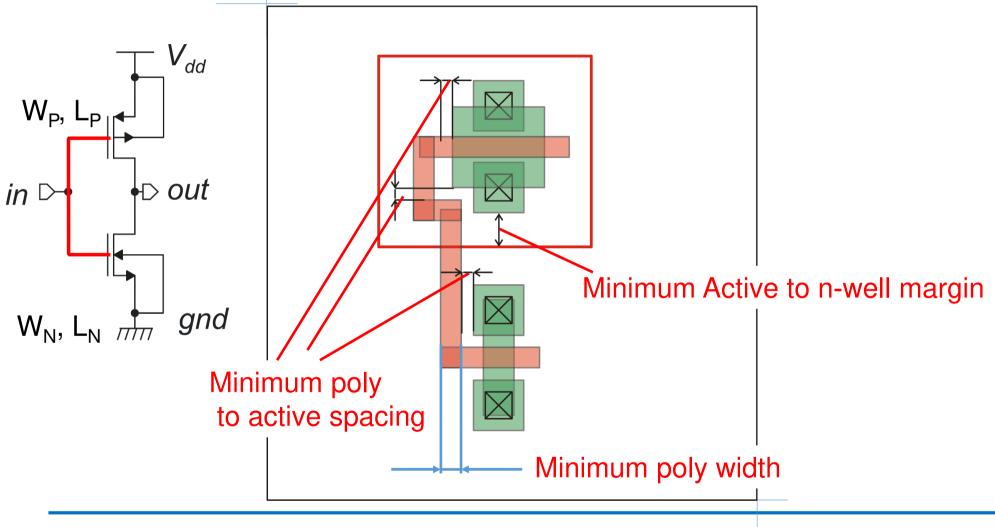


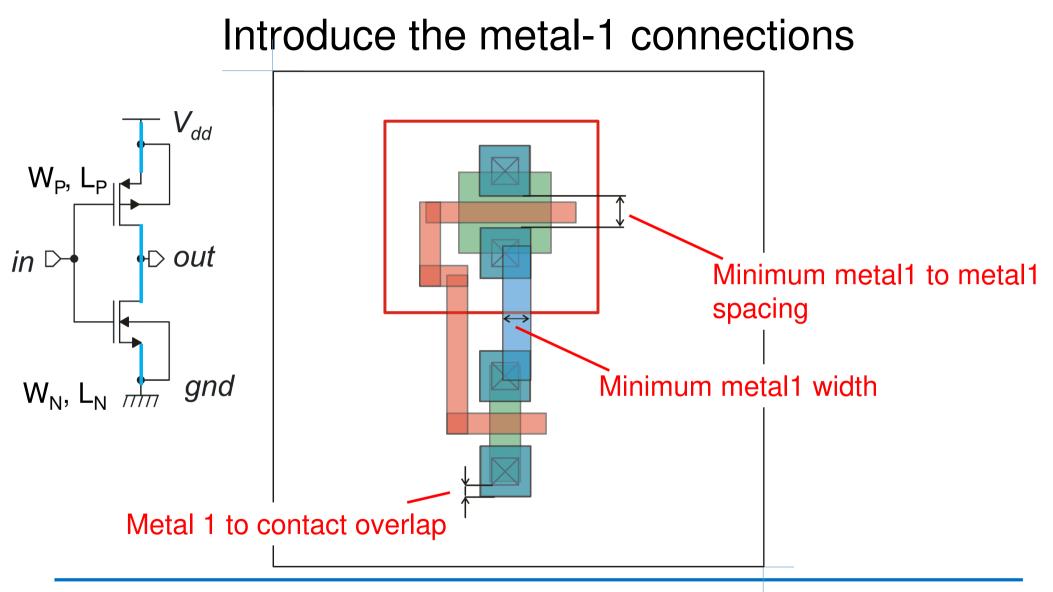


### Reduce the active extension to the minimum

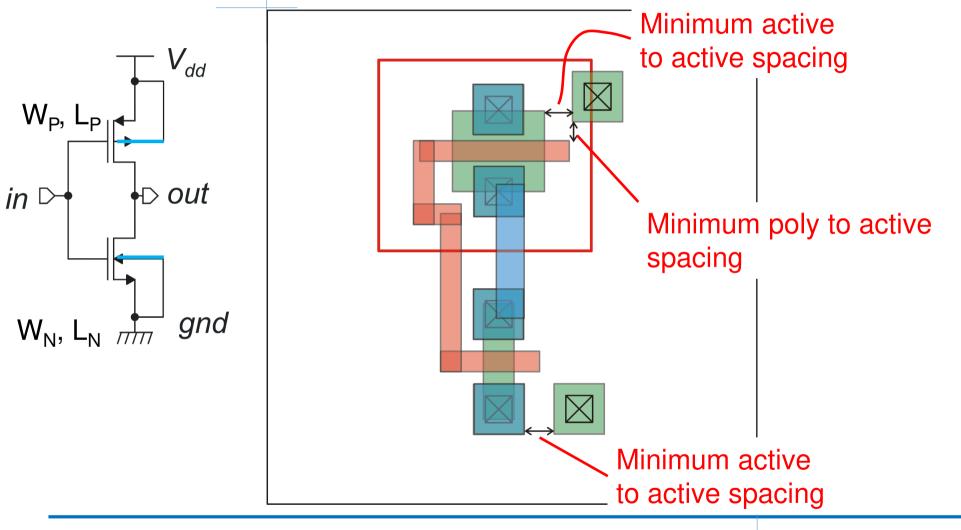


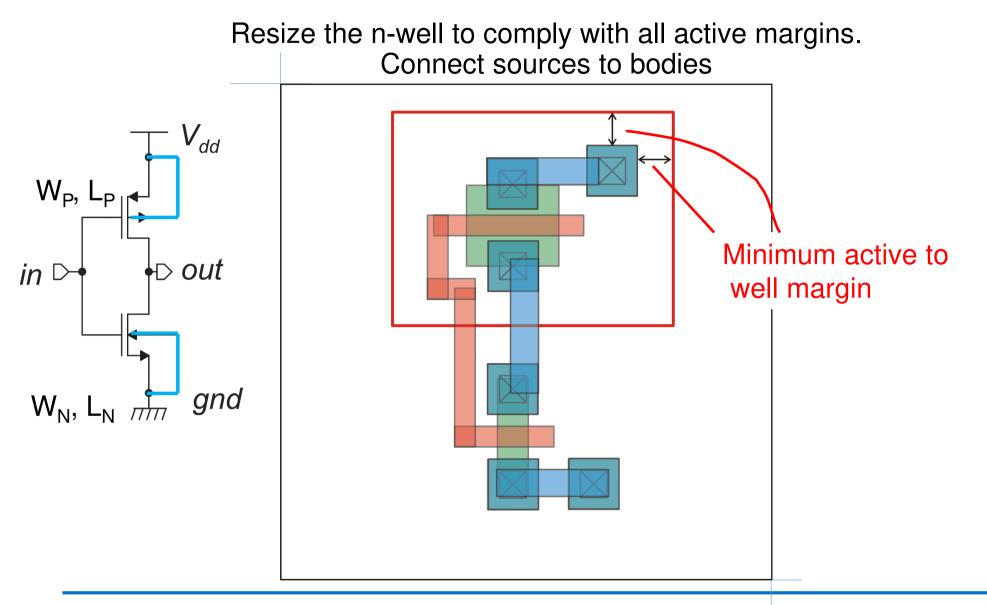
## Connect the gates of the n-MOS and p-MOS



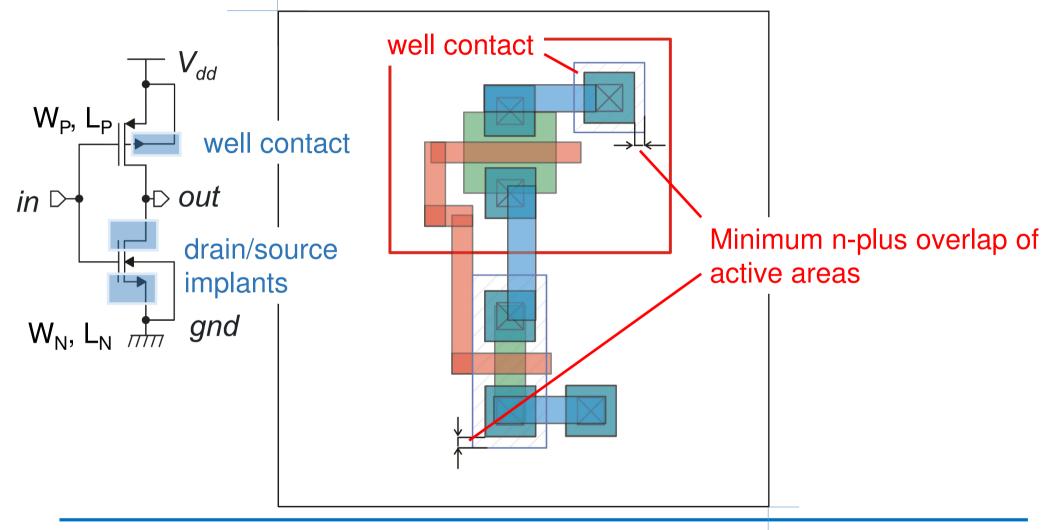


### Introduce the substrate and n-well contacts

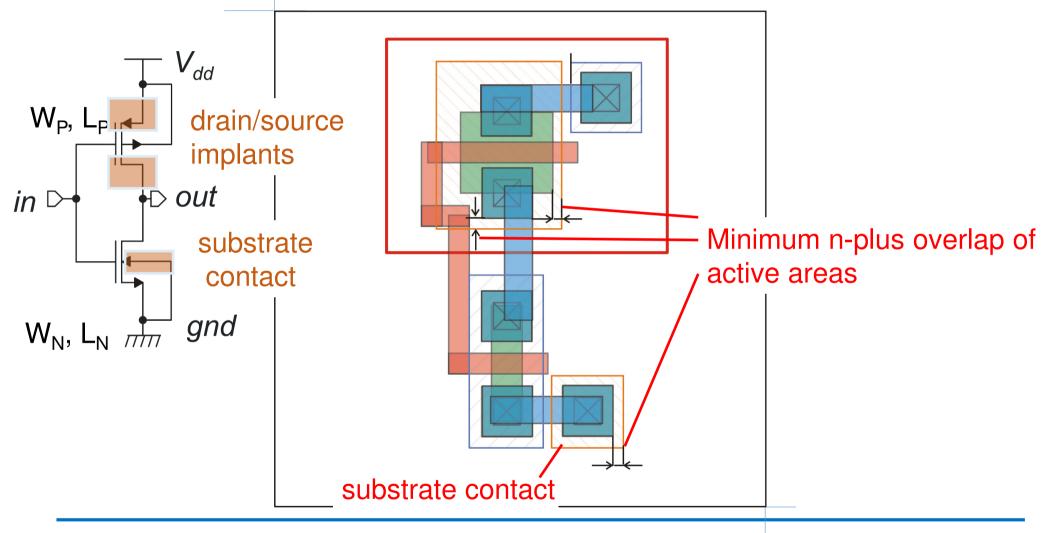




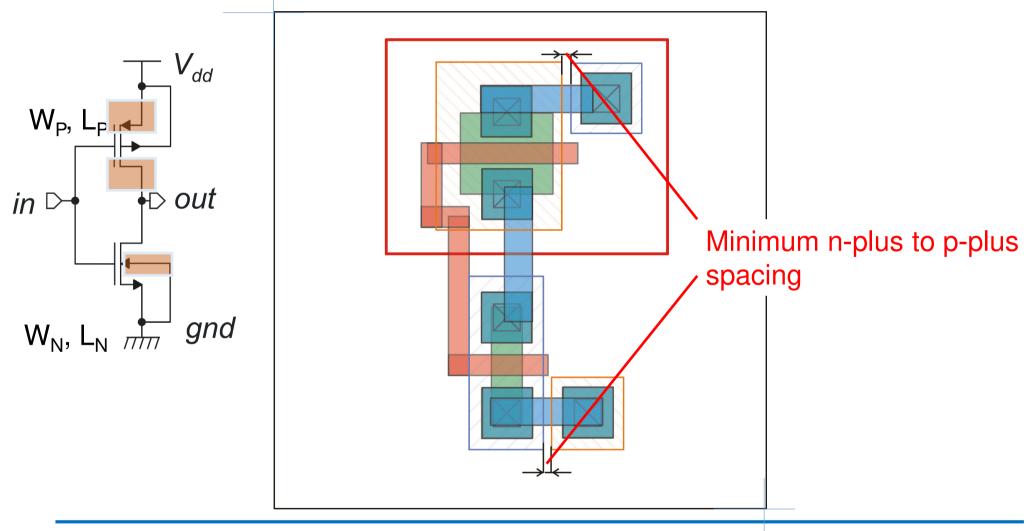
## Cover all n-plus active areas with n-plus implant

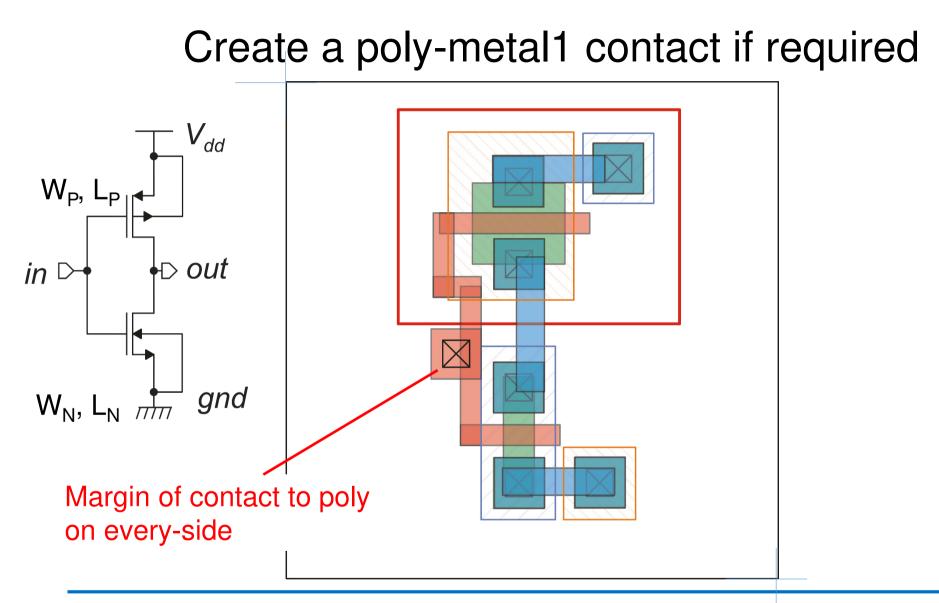


### Same thing with p-plus active areas (p-plus implant)



### Same thing with p-plus active areas (p-plus implant)





# Create a poly-metal1 contact if required

